

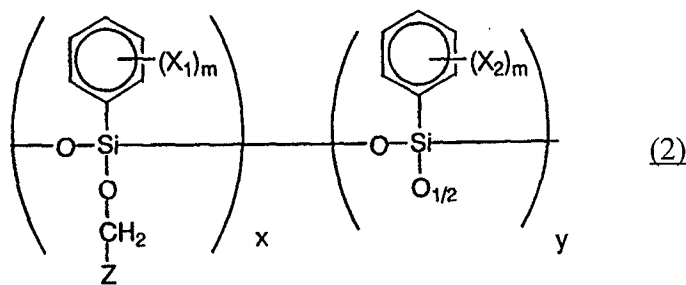
Amendments to the Claims:

Claims 1- 6 (Canceled).

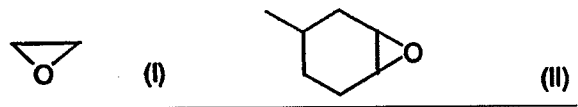
7. (Currently amended) A method of forming a polymer optical waveguide pattern, comprising the steps of:

applying and drying a photosensitive composition for optical waveguides;
irradiating said resultant photosensitive composition thin film for optical waveguides with light through a mask; and
directly forming a core-ridge pattern by wet etching said photosensitive composition thin film;

wherein the photosensitive composition for optical waveguides ~~as claimed in Claim 5 is used as said photosensitive composition for optical waveguides~~ comprises an organic oligomer and a polymerization initiator, said organic oligomer being a silicone oligomer represented by the following formula (2):



wherein X_1 and X_2 may be the same as or different from each other, and denote hydrogen, deuterium, halogen, an alkyl group or an alkoxy group; m is an integer from 1 to 5; x and y designate the proportion of respective units, and y is smaller than x and may be 0; and Z denotes an epoxy group shown in the following formula (I) or (II):



Claims 8- 20 (Canceled).